

REMARKS

Please reconsider this application in view of the above amendments and the following remarks.

- Claims 1-44 are pending.
- Claims 11, 12 and 20 are canceled.
- Claims 1-10, 13-19, 21 and 22-44 are rejected.

Applicant's claims recite that a compound be "implanted at a depth on a molecular level." Applicant uses the phrase "on a molecular level" to indicate that the compounds being implanted or the compounds after implantation are atomic or molecular sized rather than bulk materials. Support for this amendment can be found throughout the specification as a whole. Specifically, the specification paragraph [0016] discloses the implantation of nitrogen ions. Nitrogen ions are well-known to be atomic sized. Moreover, paragraph [0018] discloses implanting titanium in a manner similar to that of the nitrogen ions. One of ordinary skill in the art would recognize that the implantation of sputtered-off titanium would inherently involve the implantation of titanium ions, which are atomic sized.

The cited references of record do not teach implantation "on a molecular level" as Applicant uses that term. In fact, the cited references of record teach that the titanium and nitrogen materials are in bulk form.

Please remove the outstanding art rejections.

Since all claims are in a condition for allowance, please issue a Notice of Allowability so stating. If I can be of any help, please contact me.

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Respectfully submitted,

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